

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Dai et al.

Confirmation No.: 8744

Application No.: 10/800,195

Group Art Unit No.: 1752

Filed: March 12, 2004

Examiner: Sin J. Lee

For: ORGANOELEMENT RESISTS FOR EUV LITHOGRAPHY AND METHODS OF
MAKING THE SAME

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Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

**Declaration of Christopher K. Ober, Ph.D.
Under 37 C.F.R. § 1.132**

Sir/Madam:

I, Christopher K. Ober, Ph.D. declare as follows:

1. I am a named co-inventor of above-referenced United States Patent Application Serial No. 10/800,195, entitled "Organoelement Resists for EUV Lithography and Methods of Making the Same" (hereinafter "the '195 application"), filed March 12, 2004.
2. The subject matter of the '195 application was invented by Junyan Dai, Lin Wang, Franco Cerrina, Paul Nealey and me. Each of us is named as an inventor on the '195 application.
3. The publication entitled "Synthesis and Evaluation of Novel Organoelement Resists for EUV Lithography" (Dai et al. *Proceedings of SPIE* **5039**: 1164-1172 (2003)) (hereinafter "Dai et al.") is authored by Junyan Dai, Sang Ouk Kim, Paul Nealey, Victoria Golovkina, Jangho Shin, Lin Wang, Franco Cerrina and me. The authors of this publication include the present five inventors and three additional authors, Sang Ouk Kim, Victoria Golovkina and Jangho Shin.

4. To the extent that Dai et al. describes the subject matter claimed in the '195 application, the publication describes Applicants' own work. More specifically, it is noted that the portions of the article relied upon by the Examiner in the outstanding Office Action dated April 17, 2007 to reject pending Claims 20 and 21 describe Applicants' own work, and Applicants are the sole inventors of this subject matter. Sang Ouk Kim, Victoria Golovkina and Jangho Shin, who are authors of the Dai et al. publication, did not contribute to the subject matter relied upon by the Examiner to reject pending Claims 20 and 21. Accordingly, the portion of the Dai et al. publication relied upon by the Examiner to reject Claims 20 and 21 is Applicants' own work and not the work of another.

5. In accordance with customary academic practices and in recognition of their assistance, Sang Ouk Kim, Victoria Golovkina and Jangho Shin were named as co-authors of the Dai et al. publication, but they are not listed as co-inventors on the '195 application because they did not contribute to the subject matter of the claimed invention.

6. I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

Christopher K. Ober, Ph.D.

Date